

ABSTRACT OF THE DISCLOSURE:

A vacuum pump and a vacuum exhaust system are provided that can improve the cleaning efficiency of a radical generator, effectively clear reaction products accumulating in the vacuum pump with fewer radical generators, and also reduce operating costs. A radical supply port 134A is disposed adjacent to an exhaust side outlet of an exhaust mechanism 132 and provided to extend through a housing 110A, and a radical supply means 135 supplies radicals 136 into the housing 110A through the radical supply port 134A and causes the supplied radicals 136 to flow to an area in which reaction products accumulate in the exhaust mechanism 132.